Case Electrochemical Capacitor Fabrication Facility

User Rates (per week)

Extended User Rates

<table>
<thead>
<tr>
<th>Type of Use</th>
<th>Price per Week</th>
</tr>
</thead>
<tbody>
<tr>
<td>Full Consultation</td>
<td>6300</td>
</tr>
<tr>
<td>Partial Consultation</td>
<td>5000</td>
</tr>
<tr>
<td>No Consultation</td>
<td>3400</td>
</tr>
</tbody>
</table>

Internal (Federal) CWRU User Rates

<table>
<thead>
<tr>
<th>Type of Use</th>
<th>Price per Week</th>
</tr>
</thead>
<tbody>
<tr>
<td>Full Consultation</td>
<td>3500</td>
</tr>
<tr>
<td>Partial Consultation</td>
<td>2440</td>
</tr>
<tr>
<td>No Consultation</td>
<td>1330</td>
</tr>
</tbody>
</table>

1 Additional charges for material development
2 A minimum two weeks of full consultation is required for new users
3 Internal rate use is charged to overhead-bearing grants

Lab Usage Basis
The lab is reserved for a full week of fabrication work. Using standard material and processing, about 40 capacitors can be made during one-week of operation. Variations of materials, capacitors of processing will affect the number of capacitors that can be fabricated during a week. Discussions of custom needs with our staff will help determine approaches and reasonable expectations.

Full consultations
Our engineers will fabricate batches of capacitors as per customer specifications using standard materials and custom supplied specific materials. Prior discussions with staff will estimate amounts of materials needed.

Partial consultations
After training under full-consultation option for two weeks, customers can perform own work with assistance of CWRU technical staff.

No consultation
After at least one week of partial consultation option, customer uses the lab and performs own work.

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